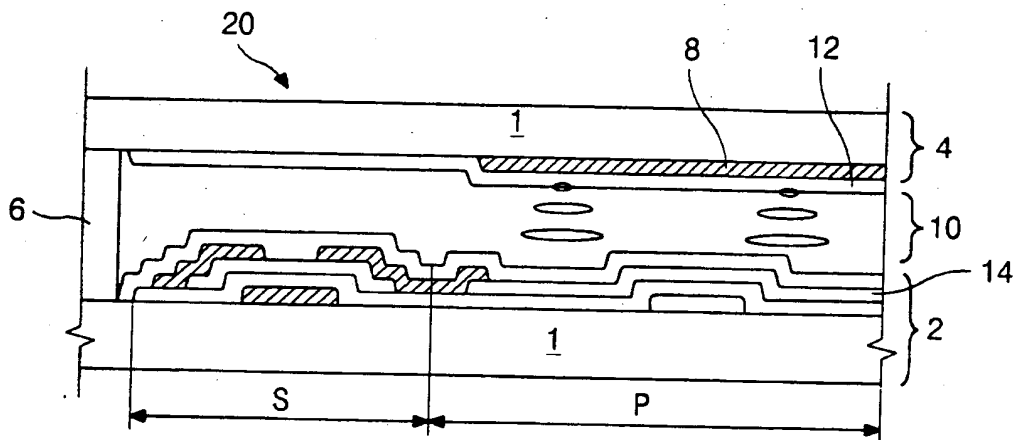
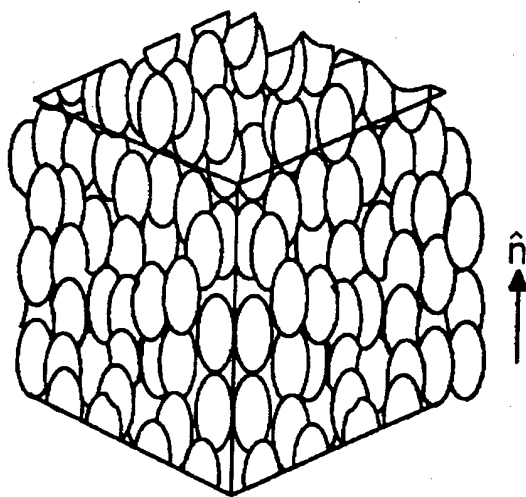


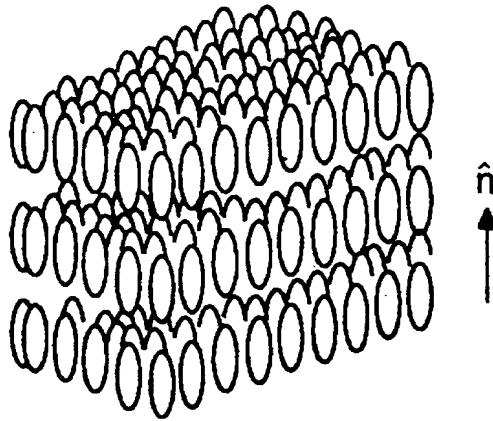
FIG. 1 is a cross-sectional view of a device 20, showing a substrate 1 with a patterned layer 2. The patterned layer 2 is formed by a series of steps 14, which are defined by a mask 6. The steps 14 are formed in a substrate 1, which is divided into a source region S and a drain region P. The steps 14 are formed in a substrate 1, which is divided into a source region S and a drain region P. The steps 14 are formed in a substrate 1, which is divided into a source region S and a drain region P.



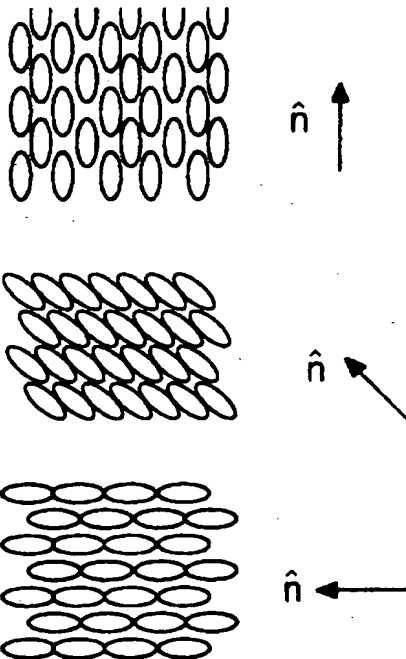
(related art)
Figure 1



(related art)
Figure 2A

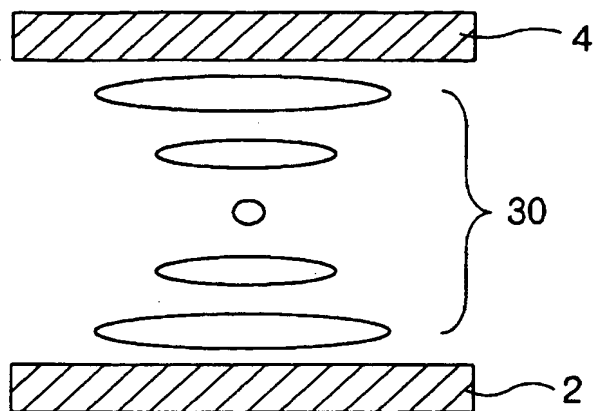


(related art)
Figure 2B

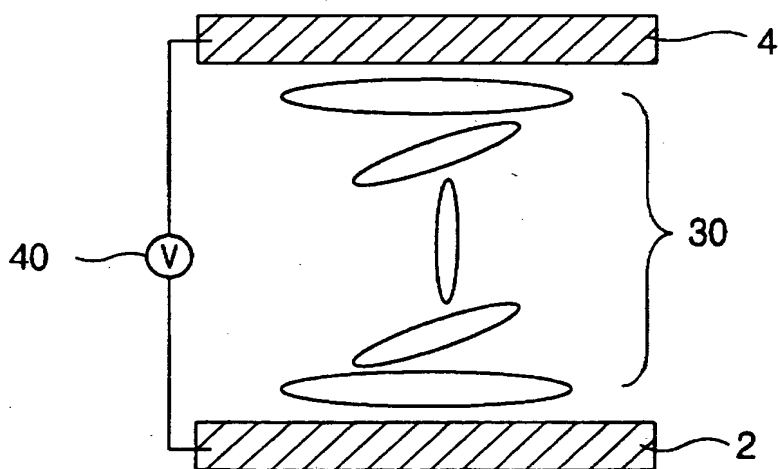


(related art)
Figure 2C

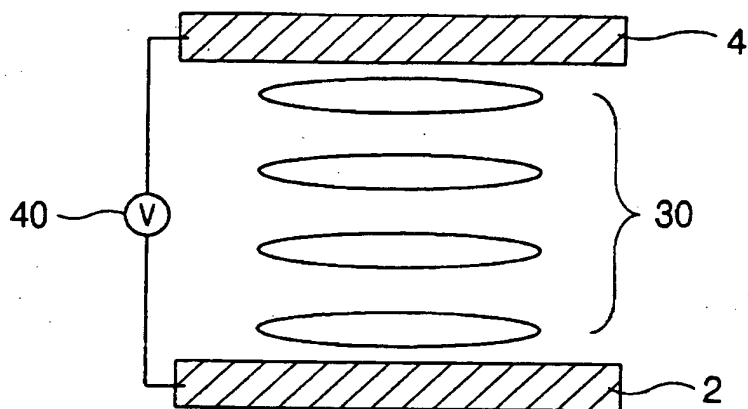
09771640, 013004



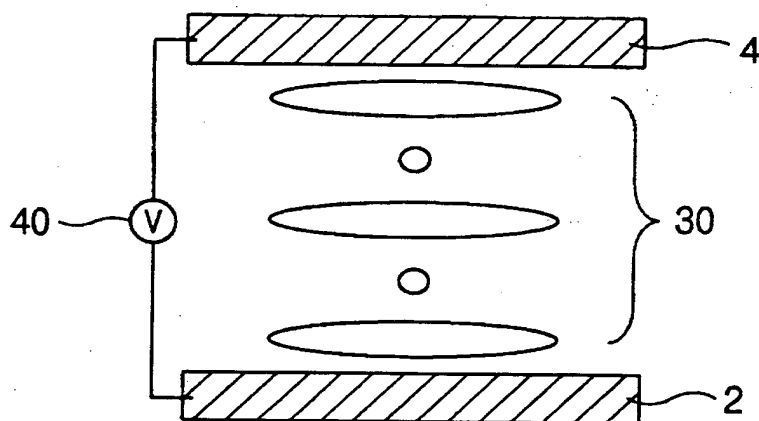
(related art)
Figure 3



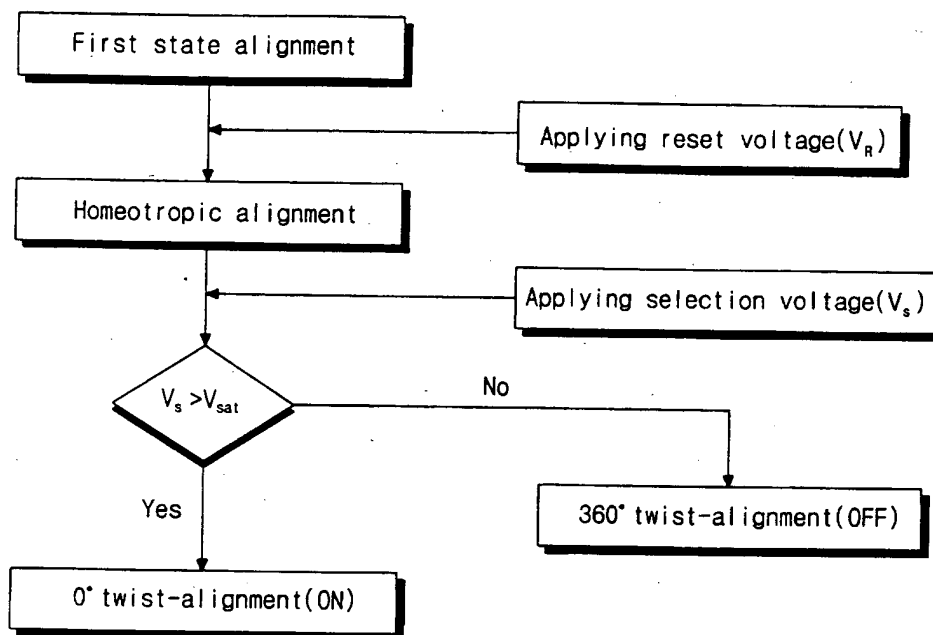
(related art)
Figure 4



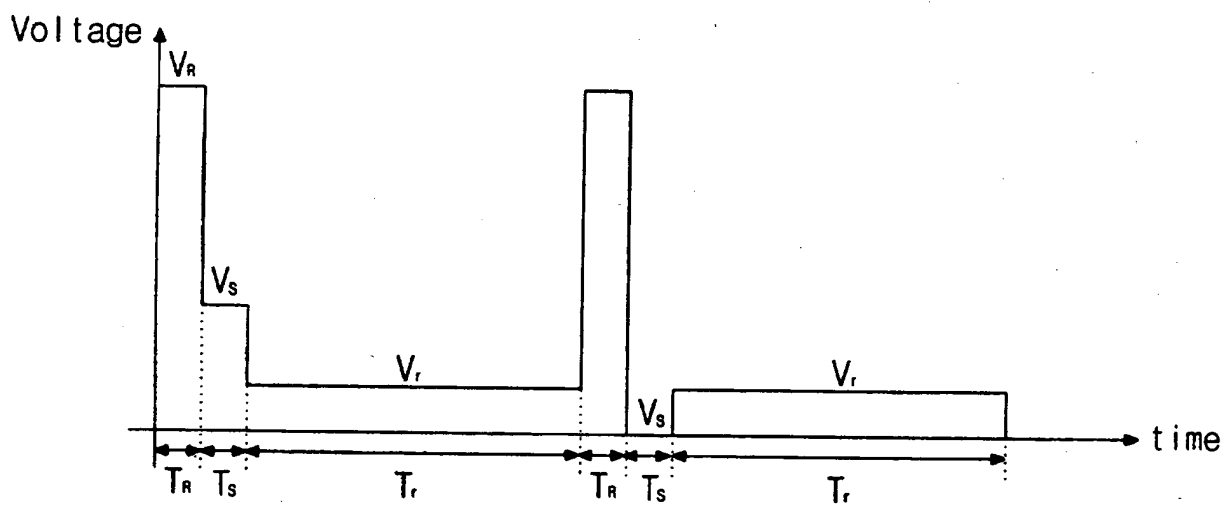
(related art)
Figure 5A



(related art)
Figure 5B



(related art)
Figure 6



(related art)
Figure 7

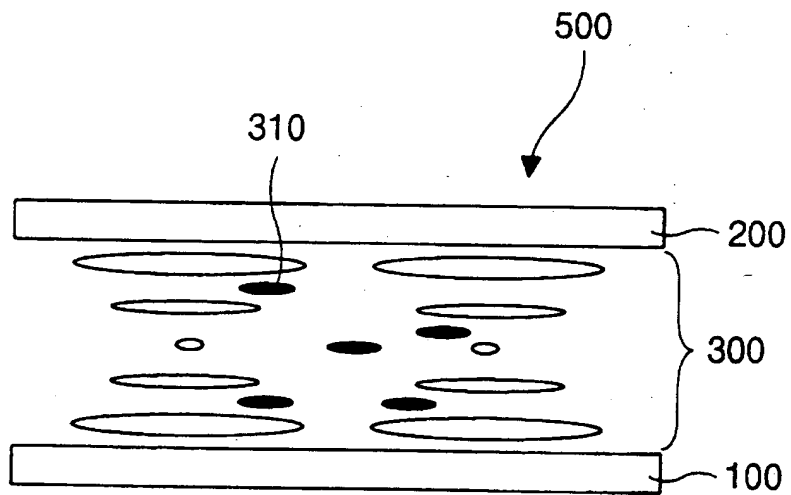


Figure 8A

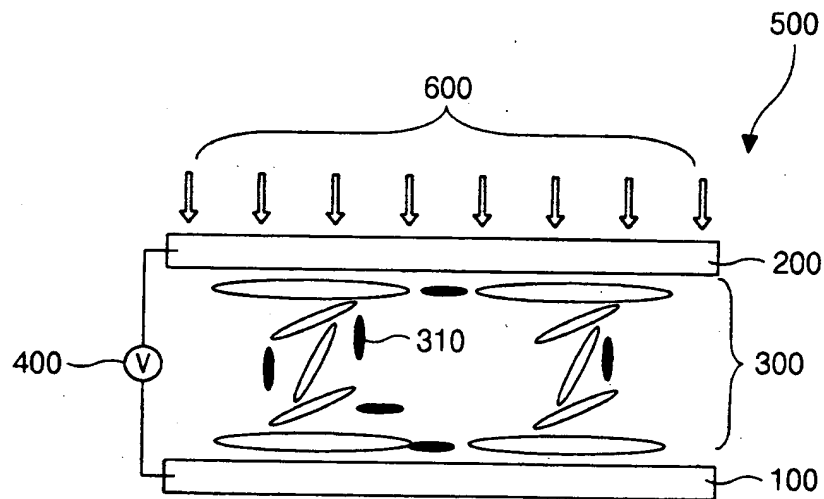


Figure 8B

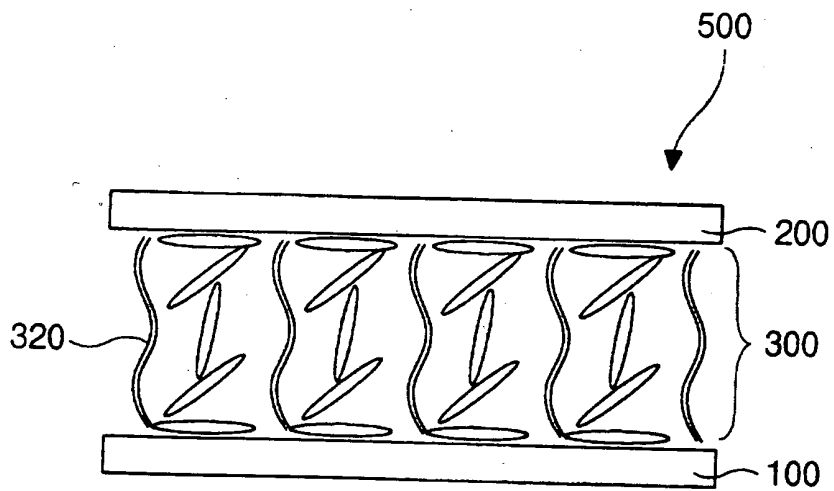


Figure 8C

FIG. 8C